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**INFORMATION DISCLOSURE STATEMENT  
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Applicant: VAN DER WERF et al.

Appln. No.: TO BE ASSIGNED

Filing Date: July 14, 2003

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Examiner: Group Art Unit:

**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PK	AR 4,613,230	09/1986	IWAI			
PK	BR 4,856,905	08/1989	NISHI			
PK	CR 6,142,641	11/2000	COHEN et al.			
PK	DR 6,151,120	11/2000	MATSUMOTO et al.			
	ER					
	FR					
	GR					
	HR					
	IR					

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
PK	JR 5-160001	06/1993	JAPAN	MIZUTANI	X			
	KR							
	LR							
	MR							
	NR							
	OR							
	PR							
	QR							
	RR							
	SR							

**OTHER (including in this order: Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

PK	TR	Chaudhuri et al., "Alignment of a multilayer-coated imaging system using extreme ultraviolet Foucault and Ronchi interferometric testing," <i>J. Vac. Sci. Technol. B</i> 13(6):3089-3093 (1995), XP 000558379		
PK	UR	Valdya et al., "Extreme Ultraviolet Lithography for 0.1 $\mu$ m Devices," <i>VLSI Technology, Systems and Applications</i> , 1999. International Symposium on Taipei, Taiwan, 8-10 June 1999, Piscataway, NJ, pp. 127-130, XP 10347511		
	VR			
	WR			
	XR			
	YR			
	ZR			
	AAR			

Examiner

*[Signature]*

Date Considered:

11/3/04

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.